

## Wafer cleaning with the new RENA 5 lane InWaClean

Short description:

Equipment for final cleaning of precleaned multi- and mono Si-wafer

Based on the experience with our well established 8 lane InWaClean for 156 mm wafer RENA has now performed detailed tests with the new 5 lane equipment and has introduced this machine to the market. The machine has a modular design so that future requirements can be fulfilled easily by the addition of modules. The InWaClean is running with a transport speed of 2.2 (1.9) m/min for multi (mono) wafer resulting in a throughput of 2800 (2400) wafer/h for 156 mm wafer. The transport rollers have no side flanges allowing a quick wafer format change. The novel dryer is supplied by side channel blowers thus reducing the running costs. In the design particular attention was turned to the easy service access of all components like rollers, gears and filters. Also for this final cleaner RENA guarantees optimum cleaning results when the specially for this application developed cleaner InWaCleanerSi010 is used.

Key words:

- 5 lane
- modular
- based on good experience with 8 lane equipment
- throughput: multi/mono 2800/2400 wafer/h
- transport speed: 2.2/1.9 m/min
- rollers without side flanges
- new dryer with side channel blower
- service friendly

Price region: 650-800 T€

Market introduction: January 09

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